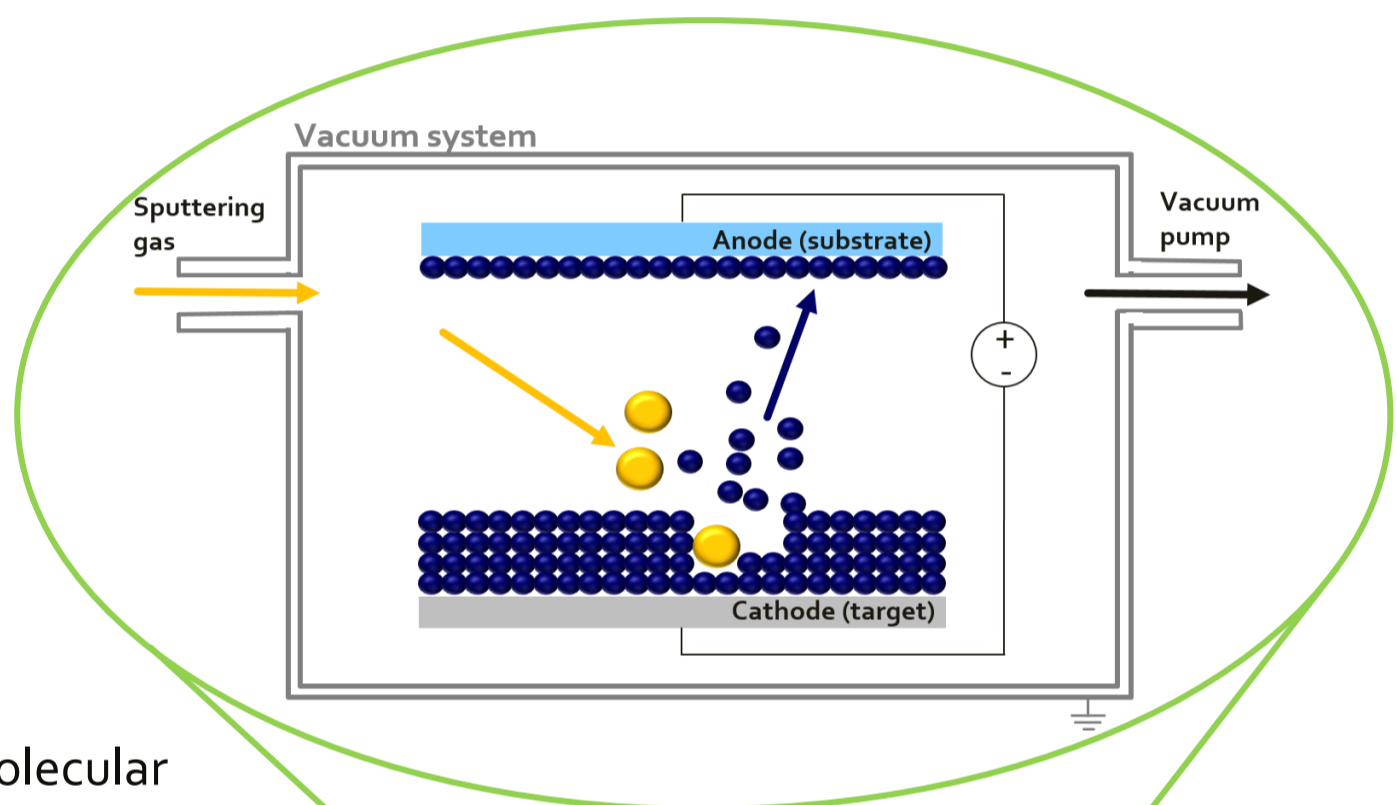


Sputtering

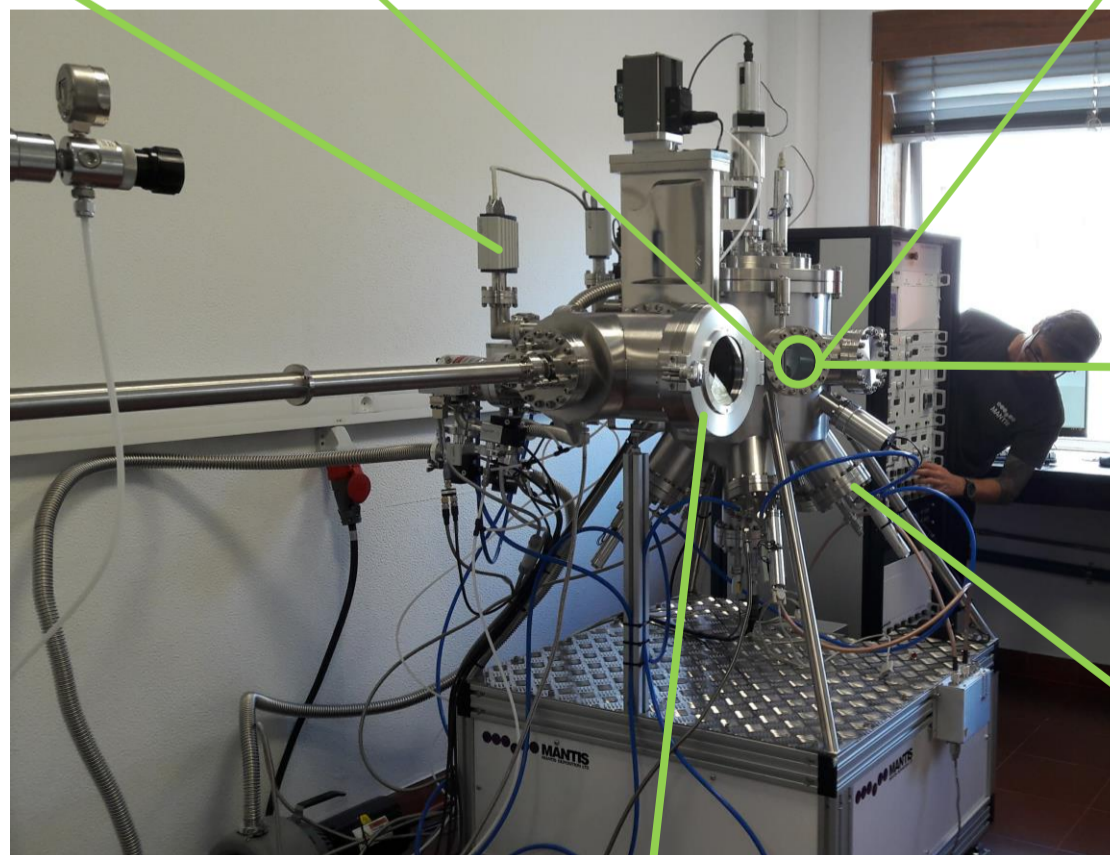
DEPOSITION OF OXIDE AND METAL THIN FILMS

Plasma formation through the application of a potential between the cathode and the anode.

The plasma created causes ionic bombardment of the target which lifts off material, leading to a deposition on the substrate.



Turbo molecular pump



Deposition chamber

Target

Load-chamber

Thin film deposition